# 1 Measurements & Parameter Extraction

## 1.1 Line Width/Misalignment

#### 1.1.1 Measured line widths

Nominal	ACTV	POLY	CONT	METAL
Linewidth	(dark field)	(clear field)	(dark field)	(clear field)
$2\mu\mathrm{m}$	3	4	1.869	2520

## 1.1.2 Misalignment

## 1.2 Four-Point Resistors [2a, 2b]

## 1.2.1 Measurement Setup

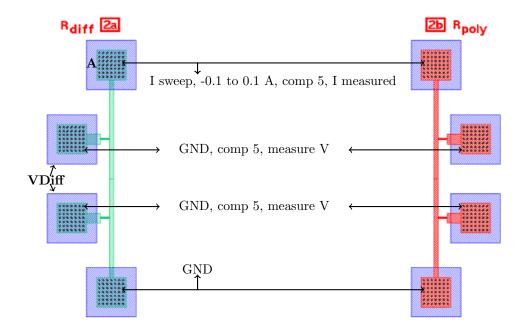


Figure 1: Device 2a is a diffusion resistor and 2b is a poly resistor.

#### 1.2.2 I-V plot for the diffusion resistor, 2a

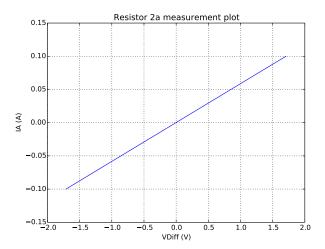


Figure 2: A plot of the measurement data taken for resistor 2a. The plot is based off of 2 data points.

From the plot above we can calculate our resistance. Note that the slope of the above plot will be equal to 1/R. Since I = V/R, where I is our dependent variable (y axis) and V is our independent variable (X axis). A resistance of  $R = 17 \Omega$  was calculated. Our width and length values are  $10\mu m$  and  $200\mu m$ . This means that

$$R_s = \frac{W}{L} R_{\text{diff}} = \frac{10}{200} 17 = 0.85 \,\Omega$$

From the previous lab report we have a junction depth of  $1 \mu m$ . This means that our Resistivity is  $\rho = R_s x_j = 0.85 \times 10^{-4}$   $\Omega$ -cm. Using the Irvin curves in Jaeger [1], we can estimate the surface concentration  $N_0 \approx 10^{21}$ . Now the mobility can be calculated using a table of values from Appendix xx.

$$\mu_e = \mu_{\min} + \frac{\mu_0}{1 + (N/N_{\text{ref}})^{\alpha}} = 92 + \frac{1268}{1 + (10^{21}/1.3 \times 10^{17})^{0.91}} = 92.37 \,\text{cm}^2/V - s$$

#### 1.2.3 I-V plot for the poly resistor, 2b

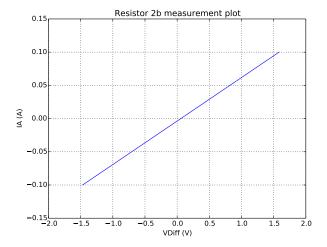


Figure 3: A plot of the measurement data taken for resistor 2b. The plot is based off of 2 data points.

From the plot above we calculate a 1/slope value of 15. Hense  $R=15\,\Omega$ . Our Resistivity is then  $\rho=R_s t_{\rm poly}$  where  $t_{\rm poly}$  is the polysilicon thickness which is 0.4  $\mu m$ , Hense  $\rho=6\,\Omega$ - $\mu m$ .

## 1.3 Four-Point Contact Resistor [17a, 17b]

#### 1.3.1 Measurement Setup

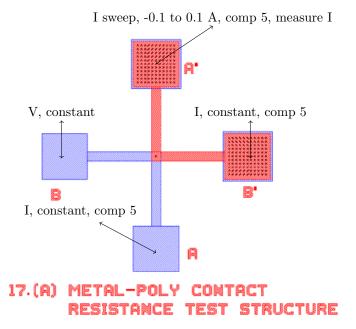


Figure 4: Measurement setup for 17a poly contact resistor. The same setup is used for the diffusion contact resistor, 17b.

#### 1.3.2 I-V plot for 17a

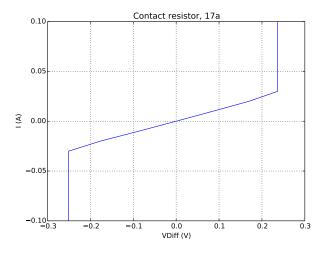


Figure 5: A plot of the measurement data taken for resistor 17a.

## 1.3.3 I-V plot for 17b

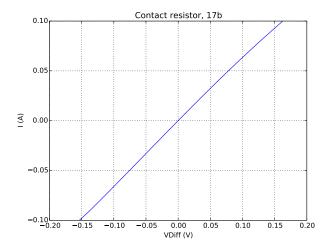


Figure 6: A plot of the measurement data taken for resistor 17b.

## 1.4 Four-Point Contact-Chain Resistor [2c, 2d]

#### 1.4.1 Measurement Setup

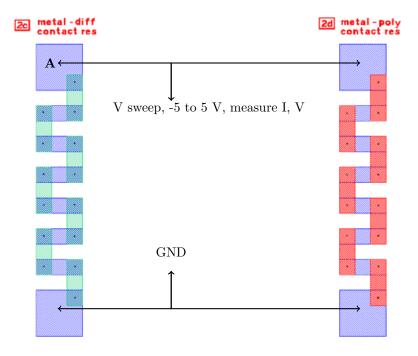


Figure 7: Chain resistor setup for diffusion and poly resistors.

## 1.4.2 b. I-V plot for diffusion resistor, 2c

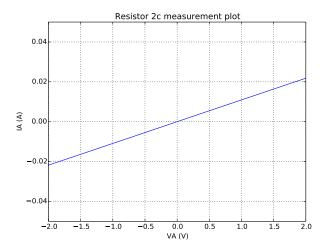


Figure 8: A plot of the measurement data taken for resistor 2c. The plot is based off of 2 data points.

- i. Extract the resistance
- ii. Extract metal-to-diffusion contact resistance

### 1.4.3 b. I-V plot for poly resistor, 2d

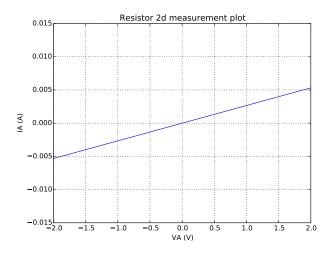


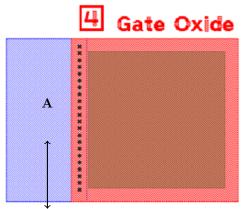
Figure 9: A plot of the measurement data taken for resistor 2d. The plot is based off of 2 data points.

- i. Extract the resistance
- ii. Extract metal-to-poly contact resistance

## 1.5 Gate Oxide Capacitor, 4

#### 1.5.1 Measurement Setup

Stage connector set to GND



V sweep, -10 to 10 V, step 0.2 V, oscillation 0.02Hz, integration medium

Figure 10: Gate capacitor setup.

## 1.5.2 C-V plot of gate oxide capacitor w/ lights ON

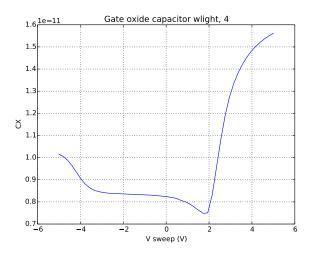


Figure 11: A plot of the measurement data taken for the gate capacitor, 4. Lights on.

Minimum capacitance

## 1.5.3 C-V plot of gate oxide capacitor w/ lights OFF

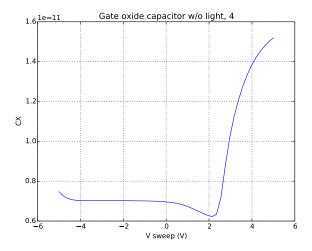


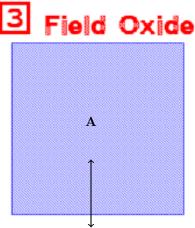
Figure 12: A plot of the measurement data taken for the gate capacitor, 4. Lights off.

minimum capacitance ...

## 1.6 Field Oxide Capacitor, 3

### 1.6.1 Measurement Setup

Stage connector set to GND



V sweep, -5 to 5 V, step 0.2 V, oscillation 0.02Hz, integration medium

Figure 13: Field oxide capacitor setup.

## 1.6.2 C-V plot of field oxide capacitor

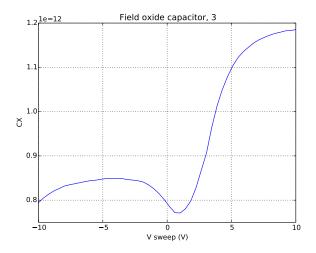


Figure 14: A plot of the measurement data taken for the field oxide capacitor, 3

Minimum capacitance

#### 1.6.3 Capacitance in the accumulation region

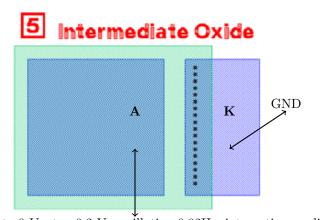
minimum capacitance ...

#### 1.6.4 Field oxide thickness

stuff...

## 1.7 Intermediate Oxide Capacitors, 5

#### 1.7.1 Measurement Setup



V sweep, -5 to 0 V, step 0.2 V, oscillation 0.02Hz, integration medium

Figure 15: Intermediate oxide capacitor setup.

#### 1.7.2 C-V plot of intermediate oxide capacitor

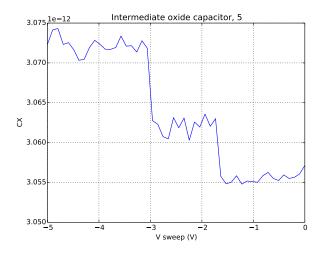


Figure 16: A plot of the measurement data taken for the Intermediate oxide, 5

stuff ...

#### 1.7.3 Capacitance in the accumulation region

stuff...

## 1.8 Diode, 7

#### 1.8.1 Measurement setups for forward and reverse operations

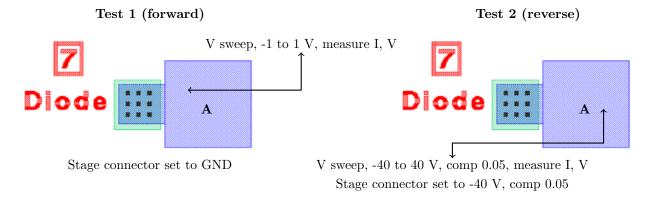


Figure 17: Two tests were performed on this diode; both measurement setups are shown above.

#### 1.8.2 I-V plots for forward and reverse operation

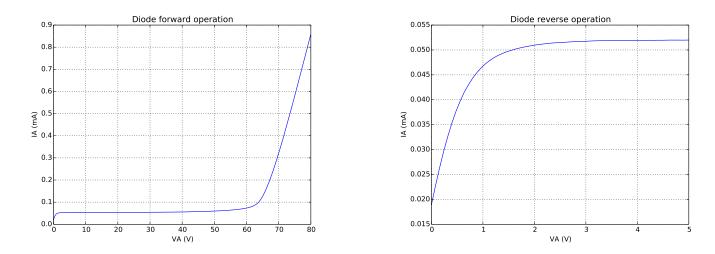


Figure 18: Plots of forward and reverse operation of Diode 7.

#### 1.8.3 Extract the turn-on voltage and the series resistance

## 1.9 MOSFETs of Varying Length, [8a-d]

#### 1.9.1 Measurement setups

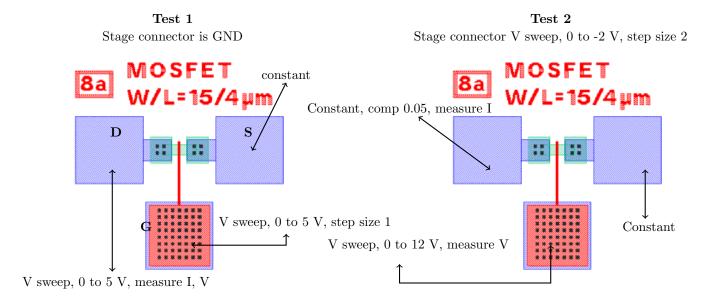


Figure 19: Measurement setup for Mosfet 8a. The same setup is used for Mosfets 8a-d. The only difference is the channel length which changes from 4 (8a) to 6 (8b) to 8 (8c) to 10 (8d) microns.

## 1.9.2 Plots of $I_D$ - $V_D$ , sweeping $V_G$

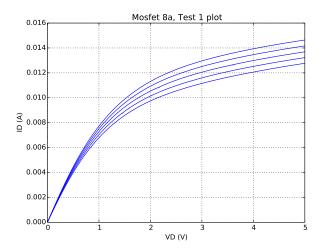


Figure 20: Test 1 for Mosfet 8a

Calculate stuff here...

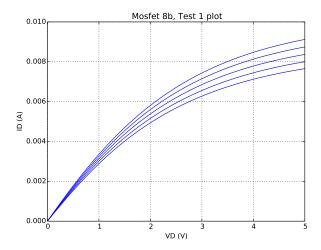


Figure 21: Test 1 for Mosfet 8b

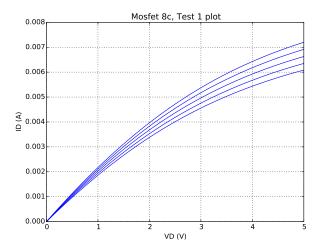


Figure 22: Test 1 for Mosfet 8c

Calculate stuff here...

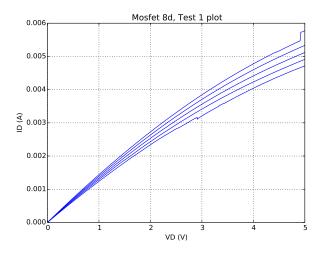


Figure 23: Test 1 for Mosfet 8d

## 1.9.3 Plots of $I_D$ - $V_G$ , sweeping $V_B$

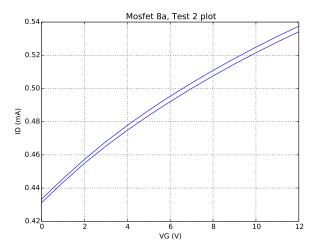


Figure 24: Test 2 for Mosfet 8a

Calculate stuff here...

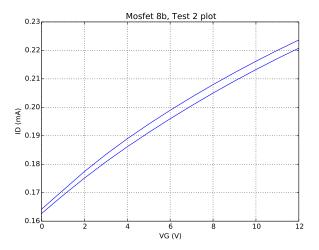


Figure 25: Test 2 for Mosfet 8b

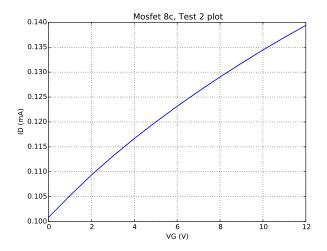


Figure 26: Test 2 for Mosfet 8c

Calculate stuff here...

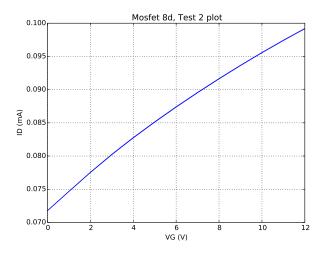


Figure 27: Test 2 for Mosfet 8d

## 1.10 MOSFETs of varying width [9a-c]

#### 1.10.1 Measurement setup

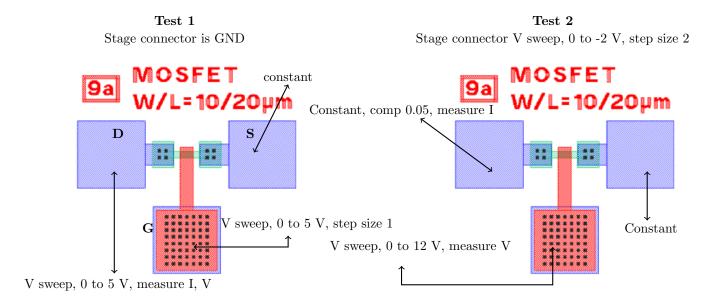


Figure 28: Measurement setup for Mosfet 9a. The same setup is used for Mosfets 9a-c. The only difference is the channel widths which changes from 10 (9a) to 15 (9b) to 20 (9c) microns.

#### 1.10.2 Plots of $I_D$ - $V_D$ , sweeping $V_G$

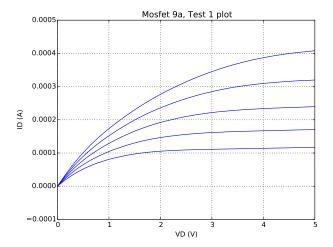


Figure 29: Test 1 for Mosfet 9a

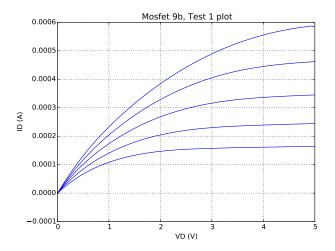


Figure 30: Test 1 for Mosfet 9b

Calculate stuff here...

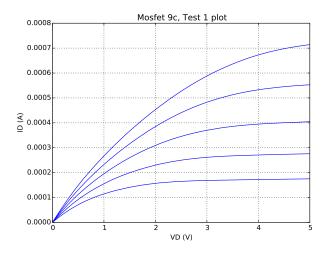


Figure 31: Test 1 for Mosfet 9c

## 1.10.3 Plots of $I_D$ - $V_G$ , sweeping $V_B$

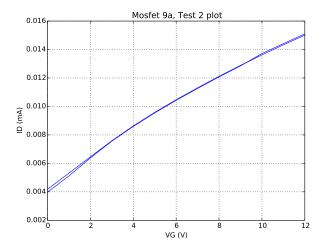


Figure 32: Test 2 for Mosfet 9a

#### Calculate stuff here...

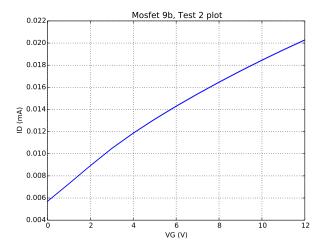


Figure 33: Test 2 for Mosfet 9b

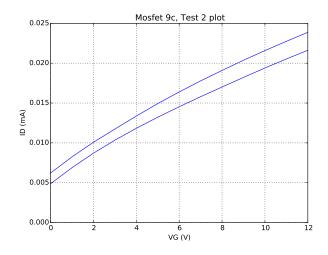


Figure 34: Test 2 for Mosfet 9c

Calculate stuff here...

## 1.11 Large MOSFET, 10

## 1.11.1 Measurement setup

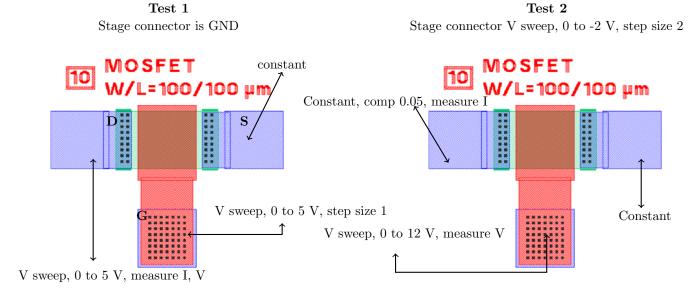


Figure 35: Measurement setup for Mosfet 10. This mosfet has very large dimensions compared to others.

## 1.11.2 Plots of $I_D$ - $V_D$ , sweeping $V_G$

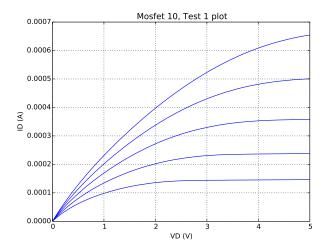


Figure 36: Test 1 for Mosfet 10

Calculate stuff here...

# 1.11.3 Plots of $I_D$ - $V_G$ , sweeping $V_B$

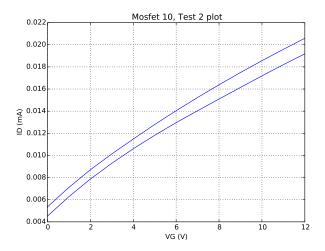


Figure 37: Test 2 for Mosfet 10

## 1.12 Inverter, 14

#### 1.12.1 Measurement setup

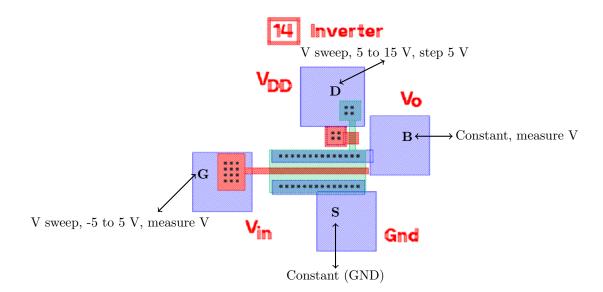


Figure 38: Setup for the inverter. Note that the source is connected to a GND and not the stage connector.

## 1.12.2 b. $V_{in} - V_{out}$ plot

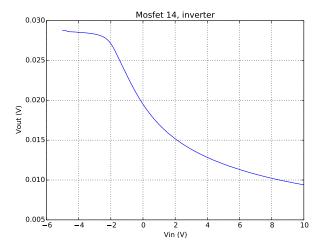


Figure 39: Plot for Inverter. Note both axis are in units of Volts.

## 1.12.3 Estimate $V_M$

calculations here....

## 2 Theoretical Calculations

## 2.1 Measured Physical Dimensions and Parameters

Parameter	Measured Value		
Field $t_{ox}$	477.2 nm		
Gate $t_{ox}$	86.5 nm		
Intermediate $t_{ox}$	320 nm		
$X_j$	1000 nm		
$X_{j,\text{lateral}}$	880 nm		
$N_D$	$10^{21}\mathrm{cm}^{-3}$		

## 2.2 Resistors [2a,2b]

## 2.3 Contact Resistances [17a,17b]

From jaeger Figure 7.6 [1] we that the specific contact resistivity  $10^{-2} \mu\Omega$ -cm<sup>2</sup>. The contact area of resistors 17a and 17b is  $5\mu m$  by  $5\mu m$ . This means the theoretical contact resistance for our contact resistors is

$$R_c = \frac{\rho_c}{A} = \frac{10^{-2}\mu\Omega - \text{cm}^2}{25\mu m} = \frac{10}{25} = 0.4\Omega$$

## 2.4 Contact-Chain Resistors [2c, 2d]

#### 2.4.1 Diffusion chain resistor, 2c

 $R_c$  is the contact resistance calculated earlier and  $R_s$  is the sheet resistance calculate for the diffused resistor.  $\eta$  is a geometrical constant that has a value of 2.3

$$R_{\text{total}} = 7(\eta R_s + R_c) = 7((2.3)(R_s) + (0.4)) = ?$$

#### 2.4.2 Poly chain resistor, 2d

 $R_c$  is the contact resistance calculated earlier and  $R_s$  is the sheet resistance calculate for the poly resistor.  $\eta$  is a geometrical constant that has a value of 2.3

$$R_{\text{total}} = 7(\eta R_s + R_c) = 7((2.3)(R_s) + (0.4)) = ?$$

- 2.5 Gate/Field Oxide Capacitors[3,4]
- 2.6 Diode
- 2.7 MOSFETs
- 2.7.1 MOSFETs of varying length [8] and width [9]
- 2.7.2 Large MOSFET
- 2.8 Inverter
- 3 Discussion
- 4 Optional Questions
- 5 Appendix
- 6 References
  - 1. Jaeger, Richard. Introduction to microelectronic fabrication. New Jersey: Prentice Hall, 2002. Print.